	Application No.	Applicant(s)	\overline{C}
Notice of Allowability	10/050,014	KHASELEV ET AL.	
	Examin r	Art Unit	
	Edna Wong	1753	
Th MAILING DATE of this communication appeal claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT R of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in this ap or other appropriate communication (IGHTS. This application is subject to and MPEP 1308.	plication. If not included will be mailed in due o	d course, THIS
 The allowed claim(s) is/are 7 and 9-16. 	rar dated Becomber 1, 2005.		
The drawings filed on are accepted by the Examine The drawings filed on are accepted by the Examine The drawings filed on are accepted by the Examine	er .		
4. ☐ Acknowledgment is made of a claim for foreign priority use a) ☐ All b) ☐ Some* c) ☐ None of the:			
1. Certified copies of the priority documents have	e been received.		
2. Certified copies of the priority documents have	e been received in Application No.	·	
3. Copies of the certified copies of the priority do	ocuments have been received in this	national stage applicati	on from the
International Bureau (PCT Rule 17.2(a)).			
* Certified copies not received:			
5. Acknowledgment is made of a claim for domestic priority u reference was included in the first sentence of the specific	inder 35 U.S.C. § 119(e) (to a provis ation or in an Application Data Sheet	ional application) since	a specific
$oxed{oxed}$ (a) $oxed{oxed}$ The translation of the foreign language provisional a			
 Acknowledgment is made of a claim for domestic priority u in the first sentence of the specification or in an Application 		nce a specific reference	e was included
Applicant has THREE MONTHS FROM THE "MAILING DATE" or below. Failure to timely comply will result in ABANDONMENT of	f this communication to file a reply co this application. THIS THREE-MOI	omplying with the requir	rements noted EXTENDABLE
7. A SUBSTITUTE OATH OR DECLARATION must be subm INFORMAL PATENT APPLICATION (PTO-152) which give	nitted. Note the attached EXAMINER es reason(s) why the oath or declara	'S AMENDMENT or NO ation is deficient.	OTICE OF
 8. ☐ CORRECTED DRAWINGS (as "replacement sheets") must (a) ☐ including changes required by the Notice of Draftspers 1) ☐ hereto or 2) ☐ to Paper No. 4. 		.948) attached	
(b) including changes required by the proposed drawing of	correction filed, which has be	en approved by the Ex	aminer.
(c) ☐ including changes required by the attached Examiner'			
Identifying indicia such as the application number (see 37 CFR 1 each sheet. Replacement sheet(s) should be labeled as such in t			oack) of
9. DEPOSIT OF and/or INFORMATION about the depo attached Examiner's comment regarding REQUIREMENT FOR T			ote the
Attachm nt(s)			
1☐ Notice of References Cited (PTO-892)	5☐ Notice of Informal Pa	tent Application (PTO-1	152)
 2 Notice of Draftperson's Patent Drawing Review (PTO-948) 3 Information Disclosure Statements (PTO-1449 or PTO/SB/08), Paper No 	6☐ Interview Summary (PTO-413), Paper No	<u> </u>
	3), 7□ Examiner's Amendm	ent/Comment	
4☐ Examiner's Comment Regarding Requirement for Deposit	8⊠ Examiner's Statemer	nt of Reasons for Allow:	ance
of Biological Material	O Othor	mo Wang_	
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Drawings

The drawings filed on January 17, 2002 are acceptable subject to correction of the informalities indicated on the "Notice of Draftsperson's Patent Drawing Review," PTO-948. In order to avoid abandonment of this application, correction is required in reply to the Office action. The correction will not be held in abeyance.

REASONS FOR ALLOWANCE

The following is an examiner's statement of reasons for allowance:

Claims 7 and 9-16 are allowable over the prior art of record because the prior art does not teach or suggest an electroplating solution for tin-bismuth plating solder coatings comprising:

a sulfonic acid electrolyte;

- a tin compound soluble in the electrolyte to form a tin sulfonate;
- a bismuth compound soluble in the electrolyte to form a bismuth sulfonate;
- a non-ionic surfactant comprising:
- (a) a polyethylene glycol-block-polypropylene glycol with a molecular weight between 2,000 and 10,000, and
- (b) a polyethylene glycol-ran-polypropylene glycol with a molecular weight between 2,000 and 10,000,

a grain refiner; and

an antioxidant.

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The prior art does not contain any language that teaches or suggests the above. *Gernon et al.* do not teach a non-ionic surfactant comprising a polyethylene glycolblock-polypropylene glycol with a molecular weight between 2,000 and 10,000, **and** a polyethylene glycol-ran-polypropylene glycol with a molecular weight between 2,000 and 10,000. Therefore, a person skilled in the art would not have been motivated to adopt the above conditions, and a prima facie case of obviousness cannot be established.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Edna Wong whose telephone number is (571) 272-1349. The examiner can normally be reached on Mon-Fri 7:30 am to 5:00 pm, alt. Fridays off.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Nam Nguyen can be reached on (571) 272-1342. The fax phone number for the organization where this application or proceeding is assigned is (703) 872-9306.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is (703) 308-

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1495.

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EW December 19, 2003